

## Title (en)

Coating compositions for use with an overcoated photoresist

## Title (de)

Beschichtungszusammensetzungen zur Verwendung mit einem beschichteten Fotolack

## Title (fr)

Compositions de revêtement destinées à être utilisées avec une résine photosensible

## Publication

**EP 1829942 A1 20070905 (EN)**

## Application

**EP 07250796 A 20070226**

## Priority

US 7778706 P 20060228

## Abstract (en)

Organic coating composition are provided including antireflective coating compositions that can reduce reflection of exposing radiation from a substrate back into an overcoated photoresist layer and/or function as a planarizing or via-fill layer. Preferred organic coating compositions of the invention comprise one or more resins that can harden upon thermal treatment without generation of a cleavage product. Particularly preferred organic coating compositions of the invention comprise one or more components that comprise anhydride and hydroxy moieties.

## IPC 8 full level

**C09D 133/14** (2006.01); **C09D 135/00** (2006.01); **G03F 7/00** (2006.01)

## CPC (source: EP KR US)

**C08L 33/066** (2013.01 - KR); **C08L 35/00** (2013.01 - EP KR US); **C08L 67/00** (2013.01 - KR); **C09D 133/064** (2013.01 - US); **C09D 133/066** (2013.01 - US); **C09D 133/12** (2013.01 - US); **C09D 135/00** (2013.01 - EP KR US); **C09D 145/00** (2013.01 - US); **C09D 167/02** (2013.01 - US); **G02B 1/11** (2013.01 - KR); **G03F 7/091** (2013.01 - EP KR US); **G03F 7/11** (2013.01 - KR); **G03F 7/2004** (2013.01 - US); **H01L 21/0276** (2013.01 - US); **C08L 33/066** (2013.01 - EP US); **C08L 67/00** (2013.01 - EP US); **C08L 2312/00** (2013.01 - EP KR US); **G03F 7/094** (2013.01 - US); **G03F 7/2041** (2013.01 - US)

## Citation (applicant)

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DOCDB simple family (application)

**EP 07250796 A 20070226;** CN 200710084492 A 20070227; JP 2007046770 A 20070227; JP 2013096761 A 20130502; KR 20070020294 A 20070228; KR 20130153678 A 20131211; TW 96106636 A 20070227; US 201615250302 A 20160829; US 71216007 A 20070228